

SUBSTITUTE ABSTRACT (June 17, 2003)

A substrate inspection system includes: a charged particle beam irradiation part; an electron image detecting part; a mapping projecting part which projects the secondary and/or reflected charge particle generated from a substrate on the electron image detecting part; and a control part. The electron image detecting part includes a charged particle multiplying device which has an entrance surface for the secondary and/or reflected charged particle, and an image grabbing element having a fluorescent body with a light receiving surface to receive the multiplied secondary and/or reflected charged particle and a fluorescent surface on which an optical image appears. The control part causes the fluorescent surface of the fluorescent body to be grounded and applies a first negative potential to the entrance surface of the charged particle multiplying device.

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